U.S. Department of Commerce, Patent and Trademark Office	Docket No.	Serial No.
(PTO Form 1449 modified)	AMAT/6392/DSM/LOW K/JW	10/010,950
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Applicant	Confirmation No.:
	Xia, et al.	5694
(Use several sheets if necessary)	Filing Date	Group
	November 13, 2001	2818

Examiner Dung Anh Le

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
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*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation YES	Translation NO
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	C2	Written Opinion from PCT/US99/22424, dated April 5, 2001.
	C3	PCT Partial International Search Report for US99/22317 dated March 21, 2000.

Examiner DLe Date Considered Feb-04

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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	C5	Dijkstra, et al. "Optimization of Anti-Reflection Layers for Deep UV Lithography", Proceeding of SPIE Optica/Laser Microlithography, Bellingham, SPIE, Volume 1674, (1992) Pages 362-375.
	C6	Omar, M.A. "Elementary Solid State Physics: Principles and Applications," Lowell Technological Institute, Addison-Wesley Publishing Company, 1975, Pages 124 & 125.
	C7	Fukuda, et al. "Highly Reliable SiOF Film Formation by ECR-CVD using SiF2H2", (1996) Symposium on VLSI Technology Digest of Technical Papers, IEEE, Pages 114-115.
	C8	PCT International Search Report for US/02/40034, dated May 19, 2003.
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